

Enhanced Super-resolution Imaging by Bilayer Aluminum Superlens in DUV Photolithography

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Introduction

- In 2000, Pendry theoretically proposed that [1], a metal planar can be used for imaging beyond diffraction limit, which was then experimentally demonstrated by Zhang et al in 2005 [2].
- Bilayer metal planar superlens has been studied for its superior imaging ability and simple structure, based on approximate effective medium theory (EMT) [3] or 3-layer MIM waveguide theory [4].
- In this poster, the photolithographic system with bilayer Al planar superlens was theoretically investigated to enhance super-resolution imaging performance, based on the five-layer waveguide theory, SPP mode cutoff method, and full-vector FDTD verification.

Single Metallic Superlens

Metallic superlens compensates exponential decay of the evanescent field away from the object by surface plasmons (SP) resonances.

The optical transfer function [5] of the 3-layer insulator-metal-insulator (IMI) system

$$\tau = \tau_1 \cdot \tau_m \cdot \tau_3$$

$$\tau_i = \exp(ik_{zi}d_i), i = 1, 3$$

$$\tau_m = \frac{t_0 t_d \exp(ik_{zm}d)}{1 - r_0 r_d \exp(2ik_{zm}d)}$$

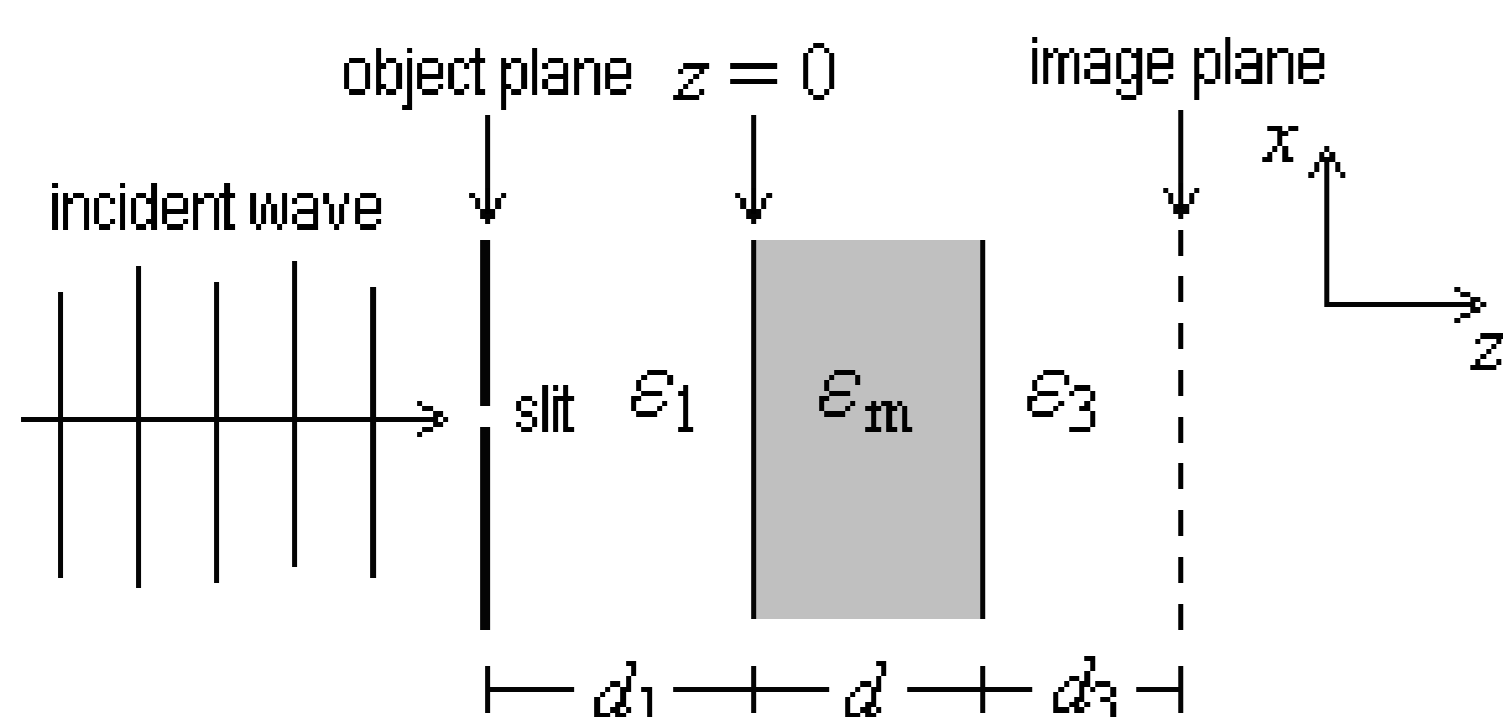


Fig. 1 Near field imaging system with the single metallic superlens

It was known that, typical transfer function of a thin Al superlens contains two amplification peaks, corresponding to two excited SPP modes.

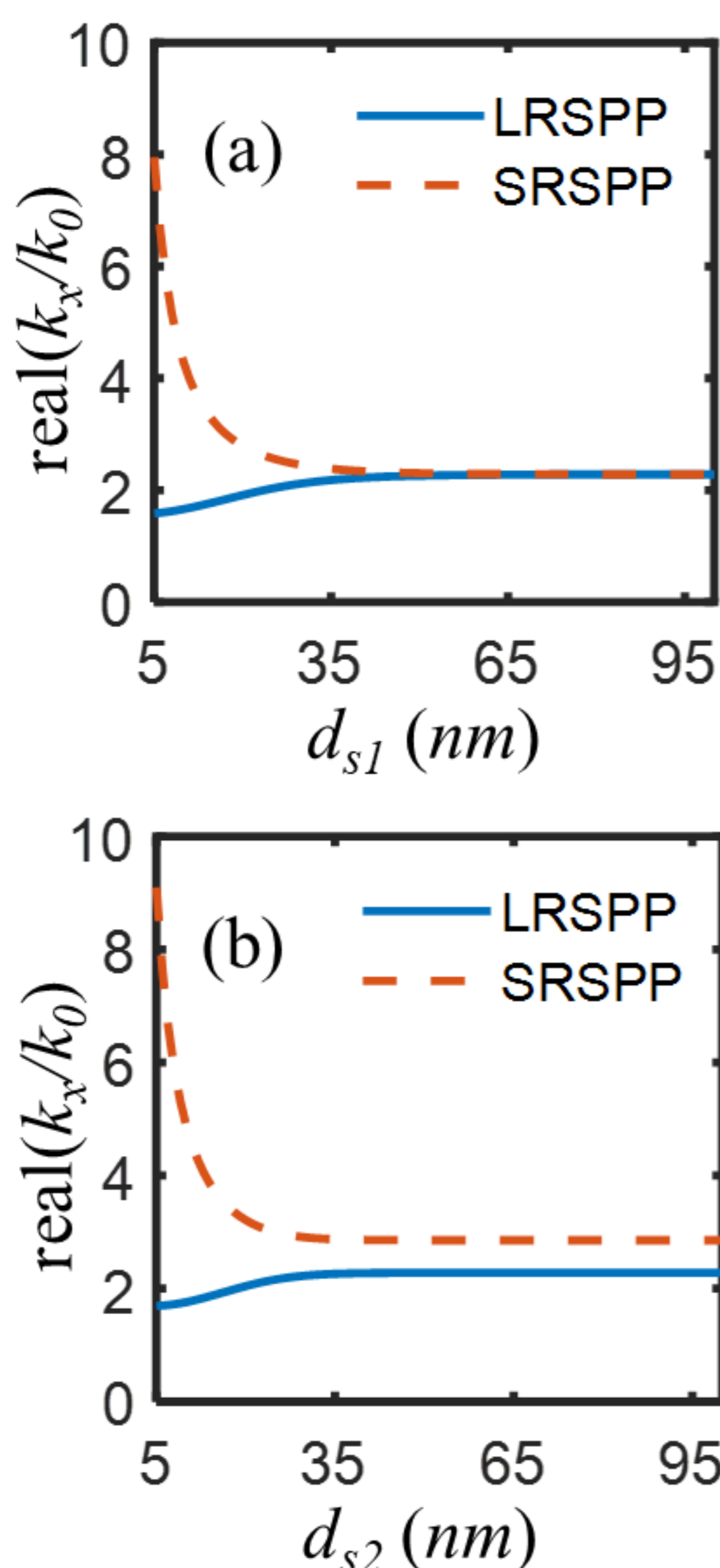


Fig. 2 Real part of effective mode indices of (a) symmetric IMI with $\epsilon_1=\epsilon_3=2.4$, and (b) asymmetric IMI with $\epsilon_1=2.4$ and $\epsilon_3=2.89$, for Al superlenses of thickness ranging from 5 nm to 100 nm.

Bilayer Metallic Superlens

From the object plane just behind the mask to the imaging plane, the imaging system with bilayer superlens is a finite-thickness metal-insulator-metal (f-MIM) structure, or 5-layer insulator-metal-insulator-metal-insulator (IMIMI).

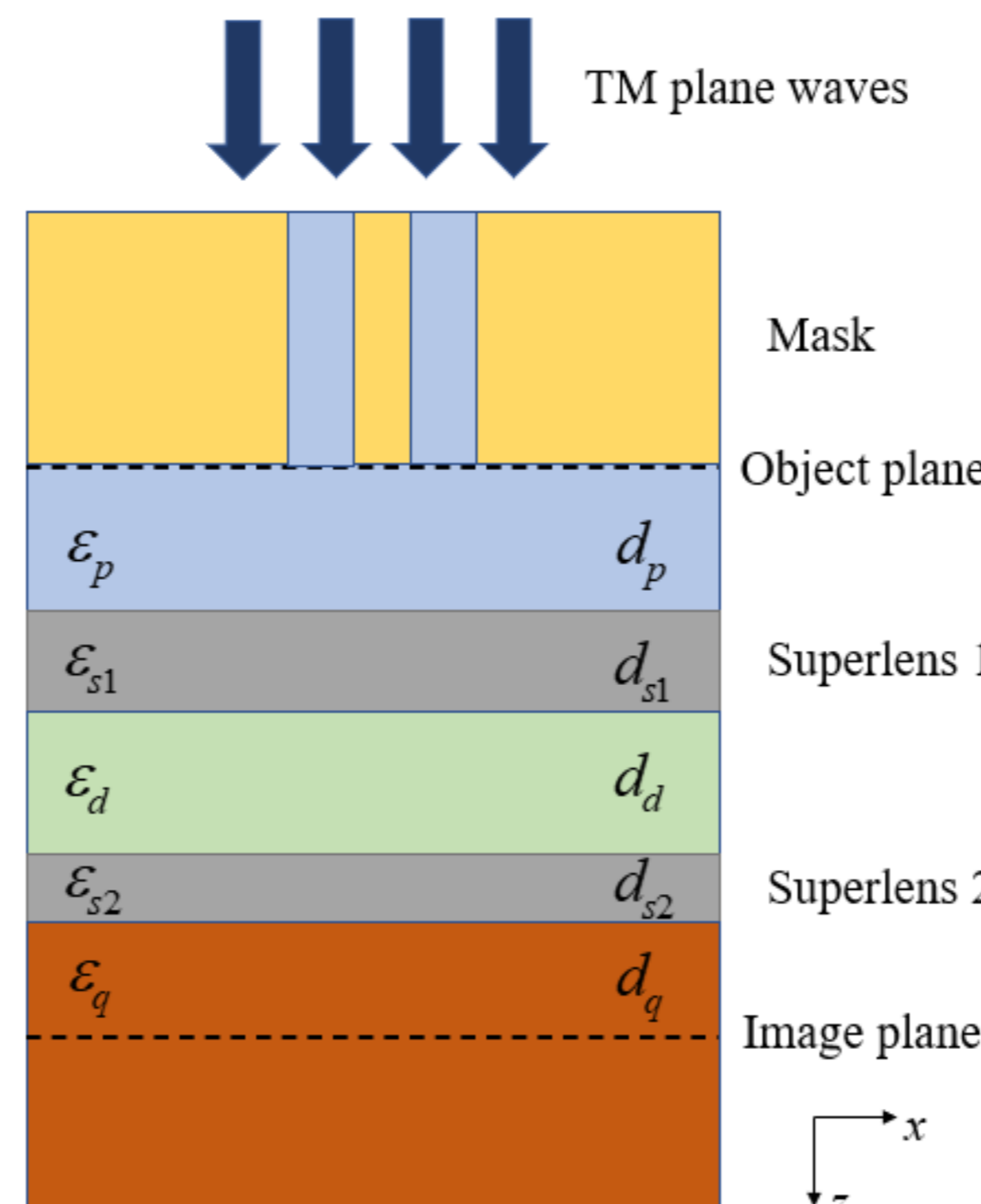


Fig. 3 Near-field photolithographic imaging system of double-layer metal superlens.

Optical transfer function from object plane to image plane:

$$\begin{aligned} \tau_{f-MIM} &= \tau_{s1} \cdot \tau_d \cdot \tau_{s2} \\ &= \frac{e_{s1} \cdot t_{p-s1} \cdot t_{s1-d}}{1 - e_{s1}^2 \cdot r_{s1-p} \cdot r_{s1-d}} \\ &\quad \cdot \frac{e_d}{1 - e_d^2 \left(\frac{r_{d-s2} + e_{s2}^2 \cdot r_{s2-q}}{1 - e_{s2}^2 \cdot r_{s2-d} \cdot r_{s2-q}} \right) \left(\frac{r_{d-s1} + e_{s1}^2 \cdot r_{s1-p}}{1 - e_{s1}^2 \cdot r_{s1-p} \cdot r_{s1-d}} \right)} \\ &\quad \cdot \frac{e_{s2} \cdot t_{d-s2} \cdot t_{s2-q}}{1 - e_{s2}^2 \cdot r_{s2-d} \cdot r_{s2-q}} \end{aligned}$$

Dispersion relation of five-layer waveguide [6]:

$$\begin{aligned} e_d^2 &= \left[e_{s2} \left(k_{z-q}/\epsilon_q - k_{z-s2}/\epsilon_{s2} \right) \left(k_{z-q}/\epsilon_q - k_{z-s2}/\epsilon_{s2} \right) \right. \\ &\quad \left. + e_{s2}^{-1} \left(k_{z-q}/\epsilon_q + k_{z-s2}/\epsilon_{s2} \right) \left(k_{z-q}/\epsilon_q + k_{z-s2}/\epsilon_{s2} \right) \right] \\ &\quad \cdot \left[e_{s1} \left(k_{z-p}/\epsilon_p - k_{z-s1}/\epsilon_{s1} \right) \left(k_{z-s1}/\epsilon_{s1} - k_{z-d}/\epsilon_d \right) \right. \\ &\quad \left. + e_{s1}^{-1} \left(k_{z-p}/\epsilon_p + k_{z-s1}/\epsilon_{s1} \right) \left(k_{z-s1}/\epsilon_{s1} + k_{z-d}/\epsilon_d \right) \right] \\ &\quad / \left[e_{s2} \left(k_{z-q}/\epsilon_q - k_{z-s2}/\epsilon_{s2} \right) \left(k_{z-q}/\epsilon_q + k_{z-s2}/\epsilon_{s2} \right) \right. \\ &\quad \left. + e_{s2}^{-1} \left(k_{z-q}/\epsilon_q + k_{z-s2}/\epsilon_{s2} \right) \left(k_{z-q}/\epsilon_q - k_{z-s2}/\epsilon_{s2} \right) \right] \\ &\quad / \left[e_{s1} \left(k_{z-p}/\epsilon_p - k_{z-s1}/\epsilon_{s1} \right) \left(k_{z-s1}/\epsilon_{s1} + k_{z-d}/\epsilon_d \right) \right. \\ &\quad \left. + e_{s1}^{-1} \left(k_{z-p}/\epsilon_p + k_{z-s1}/\epsilon_{s1} \right) \left(k_{z-s1}/\epsilon_{s1} - k_{z-d}/\epsilon_d \right) \right] \end{aligned}$$

SPP modes and MTF

IMIMI waveguide could support up to 4 SPP modes, e. g. symmetrically coupled long-range SPP (s-LRSPP), antisymmetrically coupled LRSPP (a-LRSPP), symmetrically coupled short-range SPP (s-SRSPP), and antisymmetrically-coupled SRSPP (a-SRSPP).

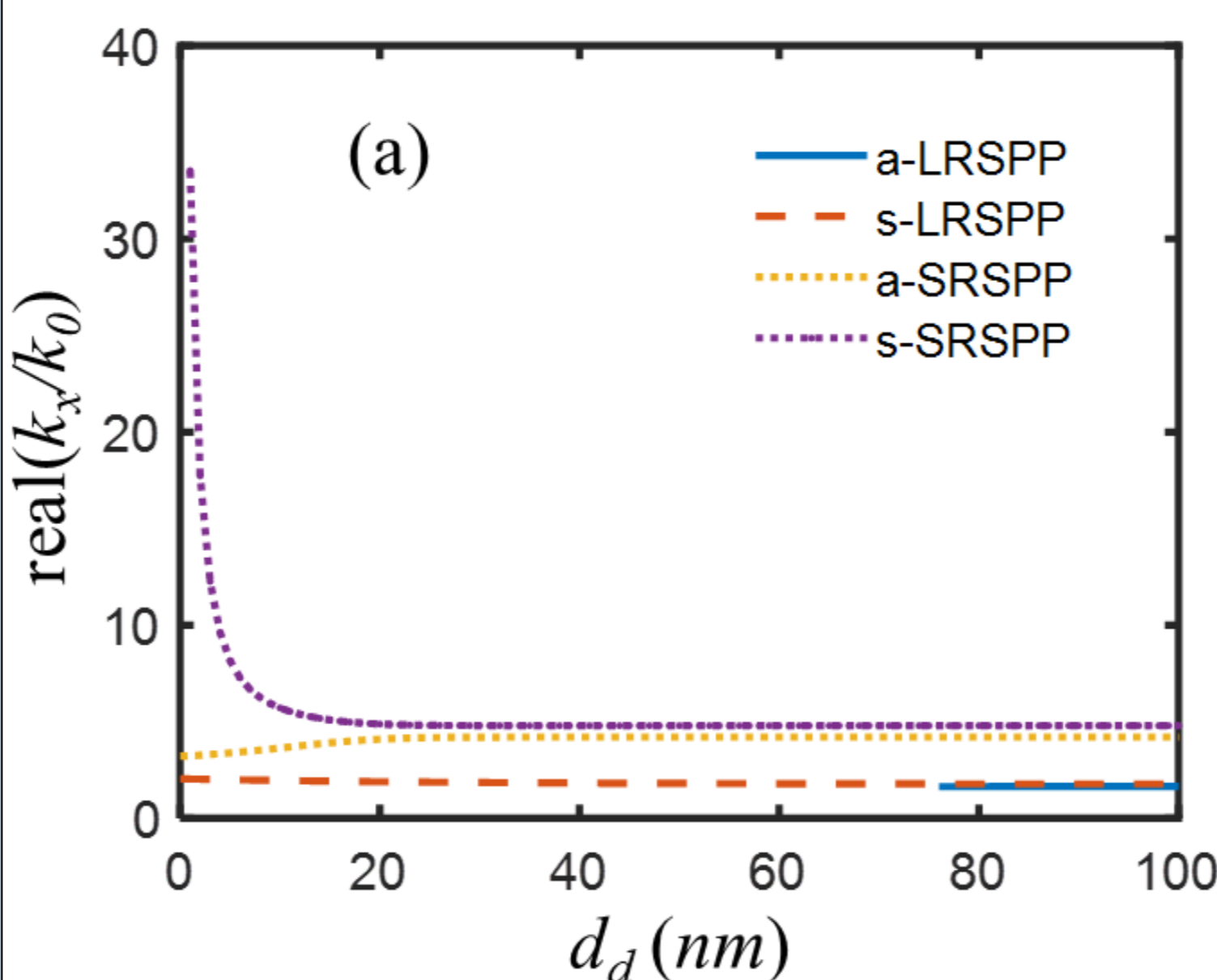
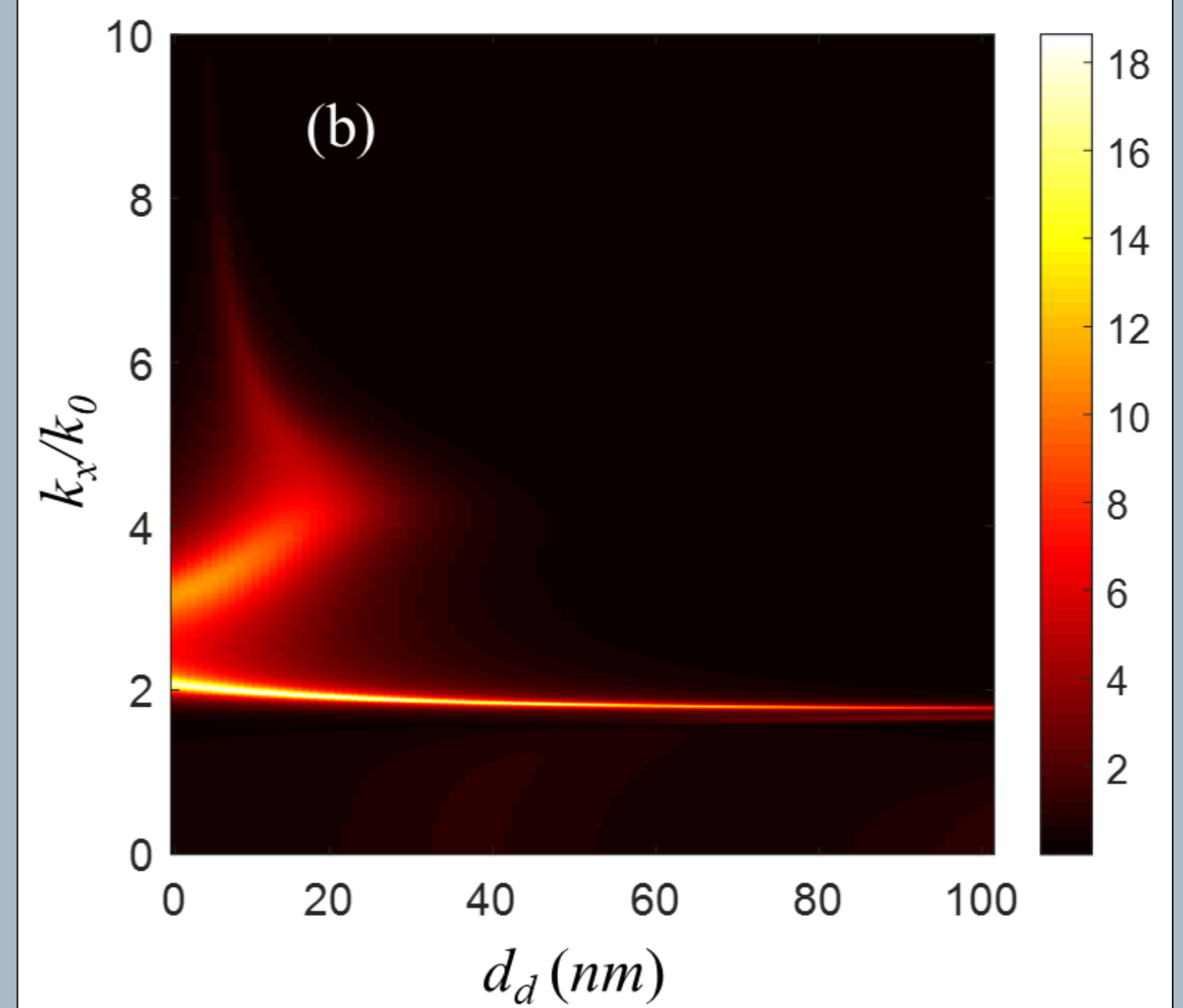


Fig. 4 (a) effective mode indices of a-LRSPP, s-LRSPP, a-SRSPP and s-SRSPP of IMIMI waveguide, and (b) the transmission coefficient of f-MIM waveguide, for two 10nm Al superlenses and a sandwiched SiO₂ layer.



The most remarkable and highest peak, located in proximity to $k_x/k_0=2$, was associated with s-LRSPP mode. This amplification would adversely affect super-resolution imaging.

s-LRSPP mode cutoff and FDTD validation

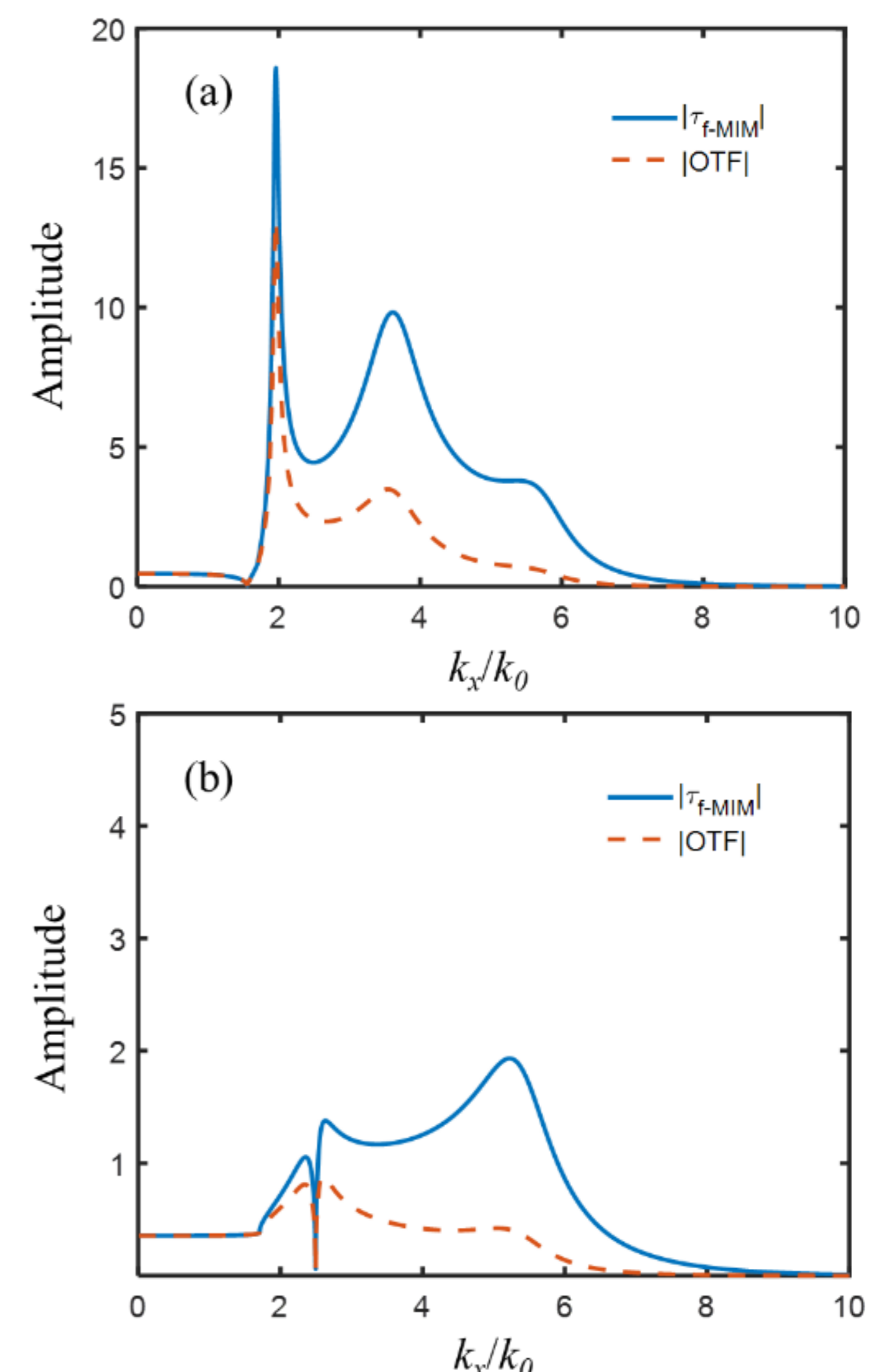


Fig. 5 The MTF (a) before, and (b) after s-LRSPP cutoff.

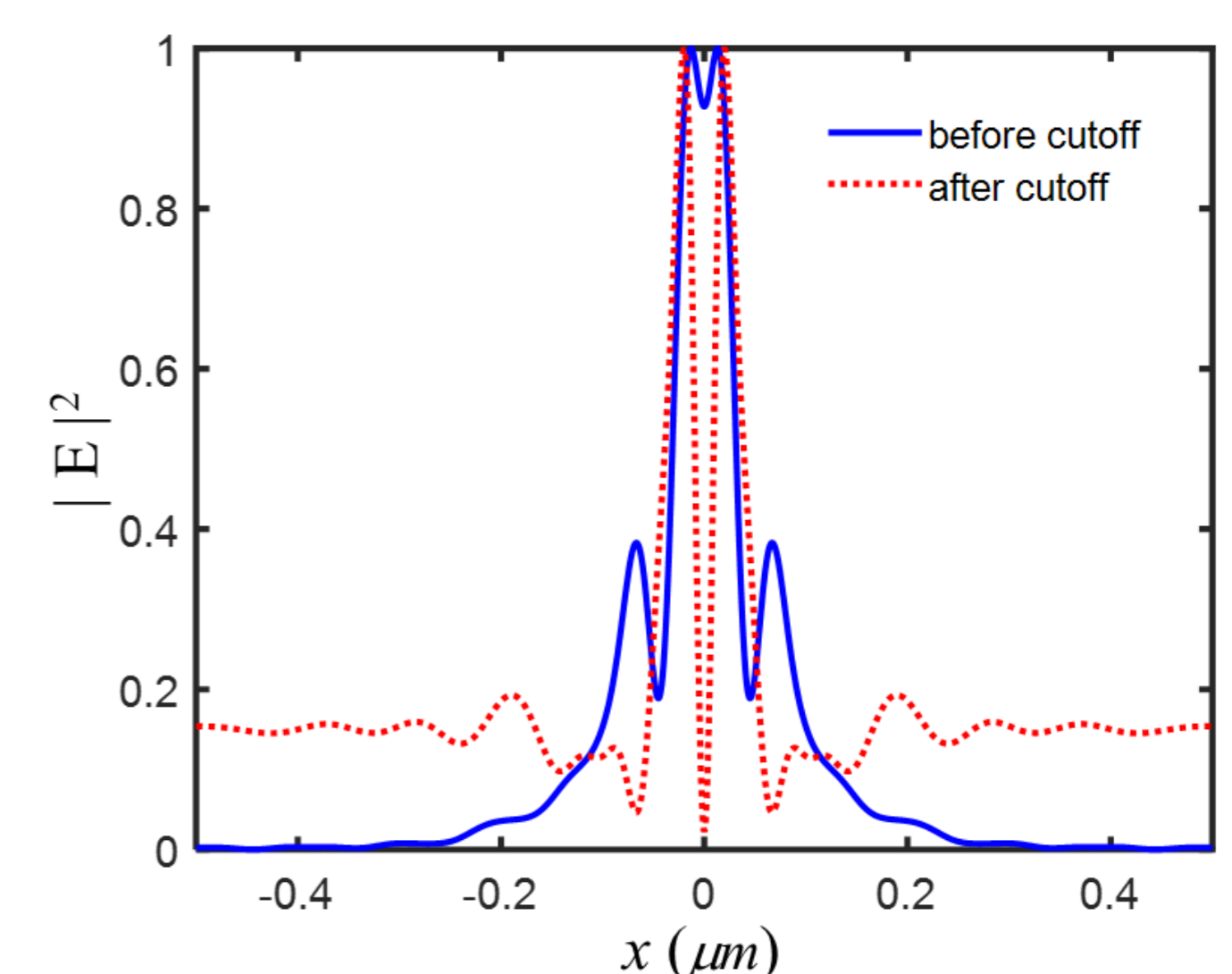


Fig. 6 For W mask of two slits with a slit width 15nm and a spacer width 15nm, the normalized electrical field intensity (a) before mode cutoff and (b) after mode cutoff, on the image plane by FDTD simulations.

Conclusion

- Intrinsic relation between transfer function of photolithographic imaging system with bilayer Al superlens and SPP modes of IMIMI waveguide.
- Cutoff symmetrically coupled long-range SPP (s-LRSPP) for improving the imaging performance.
- Improved super-resolution imaging performance (two slits with a slit width 15nm and a spacer width 15nm) was verified by full-vector FDTD simulations.

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Reference

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